

Enhanced performance in capacitive force sensors using carbon nanotube/polydimethylsiloxane nanocomposites with high dielectric properties

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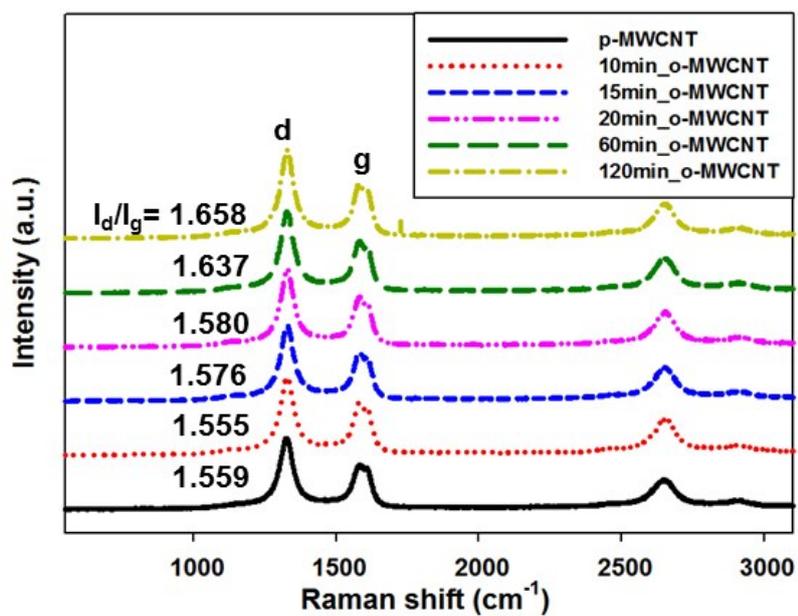


Fig. S1 Raman spectra of p-MWCNTs and o-MWCNTs treated with acid for various amount of time (10, 15, 20, 60, and 120 min).

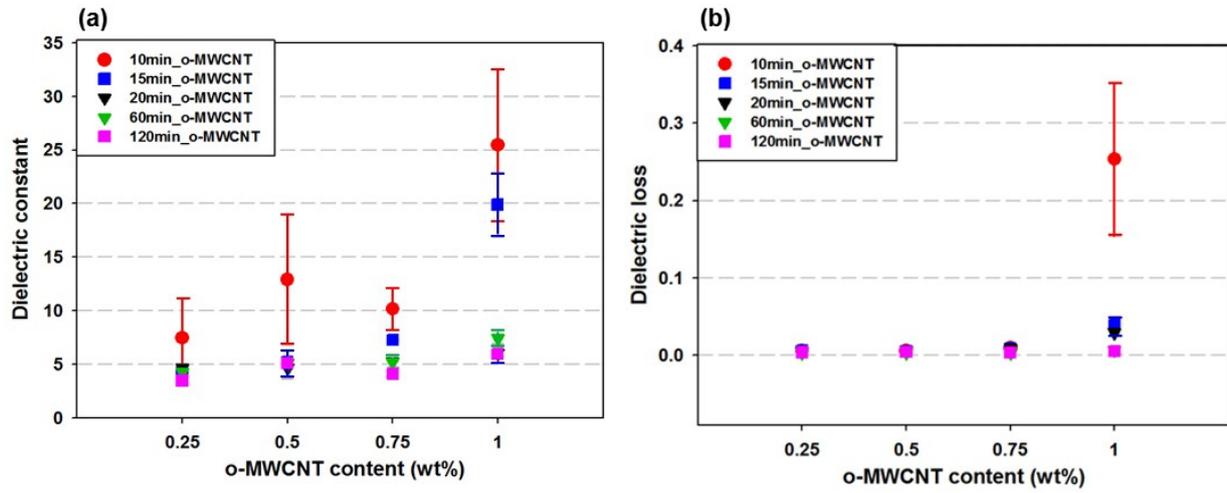


Fig. S2 (a) Dielectric constant at 100 kHz and (b) dielectric loss at 100 kHz of o-MWCNT/PDMS composites as a function of CNT contents. MWCNTs were oxidized with acid for various amount of time (10, 15, 20, 60, and 120 min).

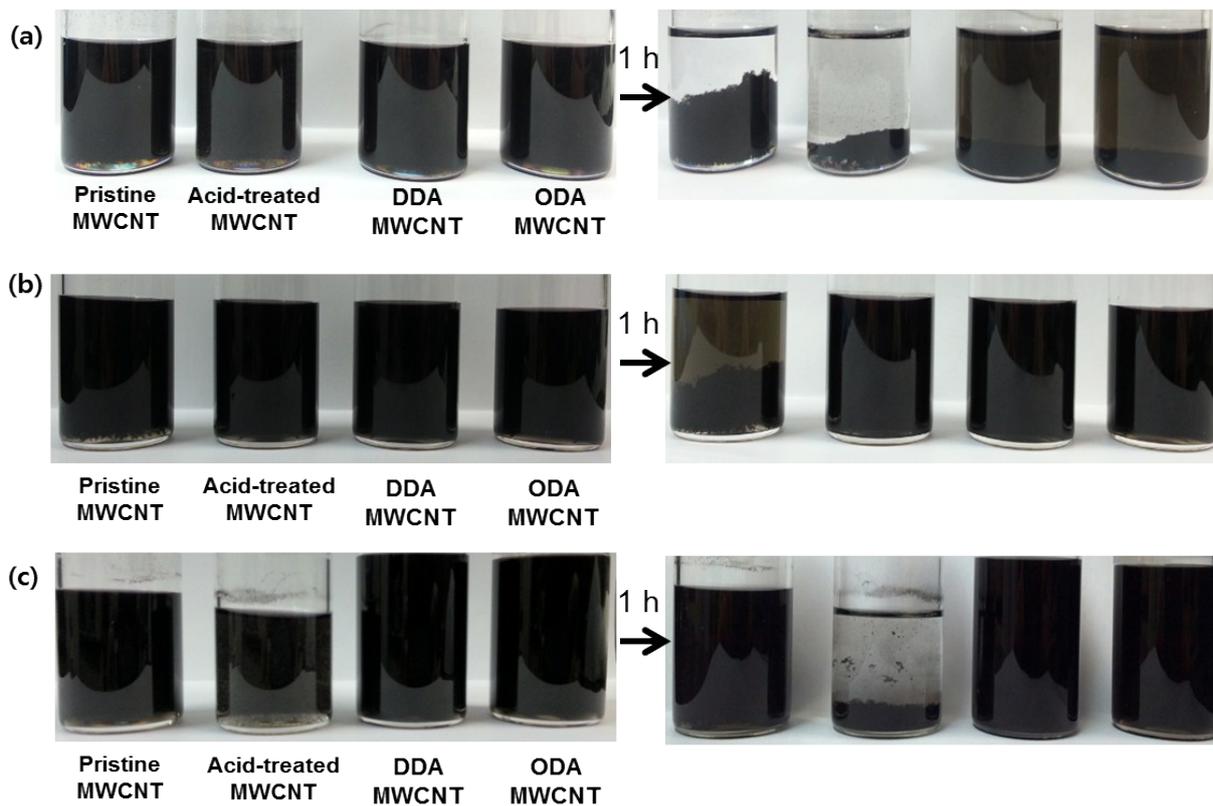


Fig. S3 Photographs of MWCNTs in (a) toluene, (b) tetrahydrofuran, and (c) chloroform after 1 h.

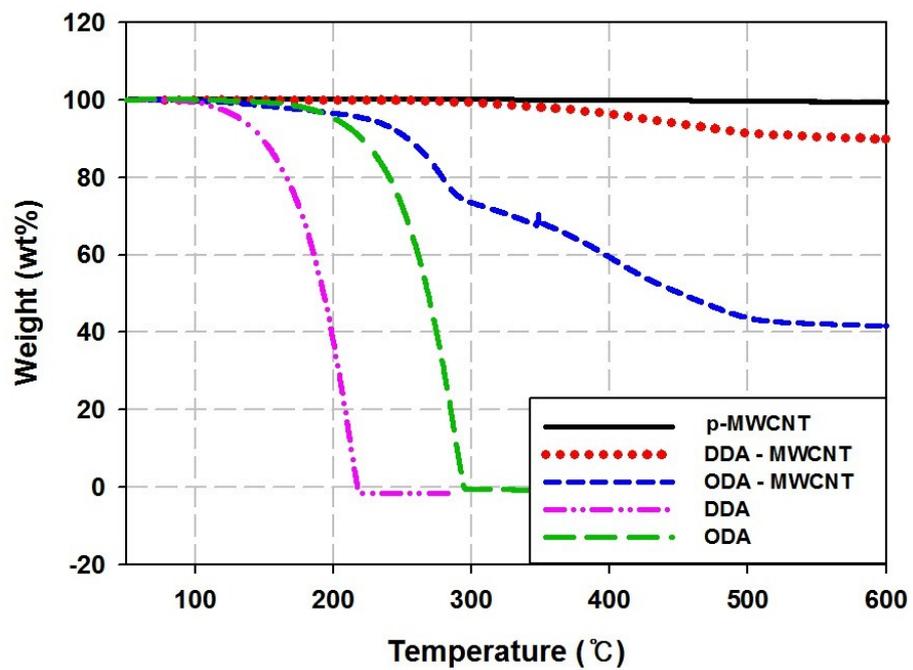


Fig. S4 TGA curves of p-MWCNT, DDA-MWCNT, ODA-MWCNT, DDA, and ODA illustrating the weight loss in the range of 50-700 °C.

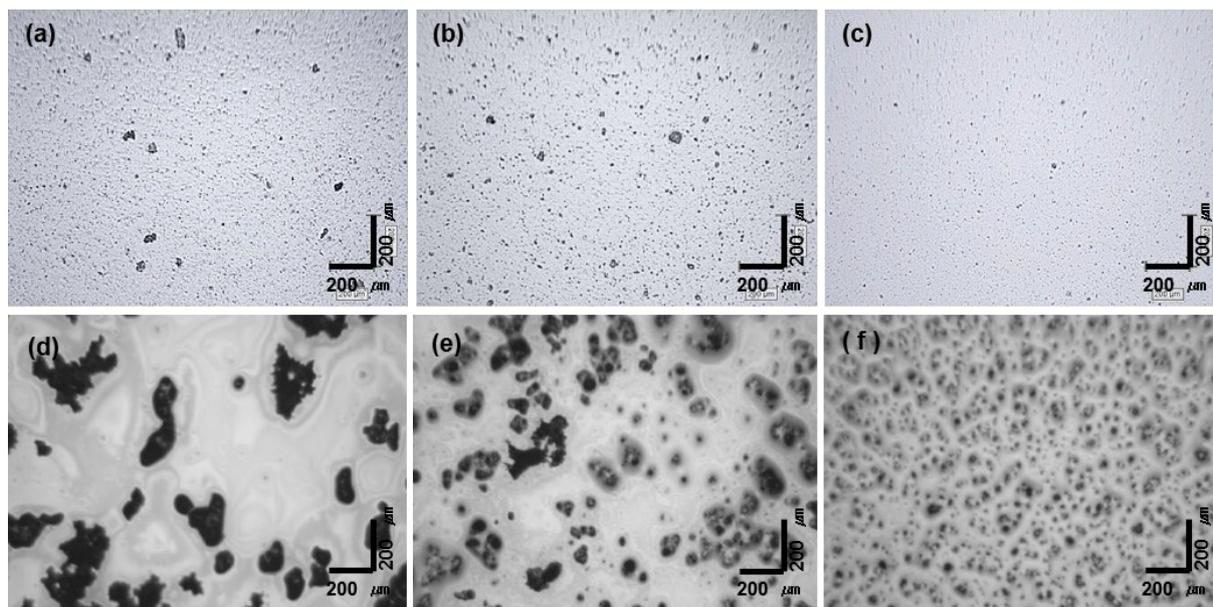


Fig. S5 Optical microscopy (OM) images of p-MWCNT, o-MWCNTs, and DDA-MWCNTs in chloroform (a, b, c) and in PDMS/chloroform mixture (d, e, f), respectively.

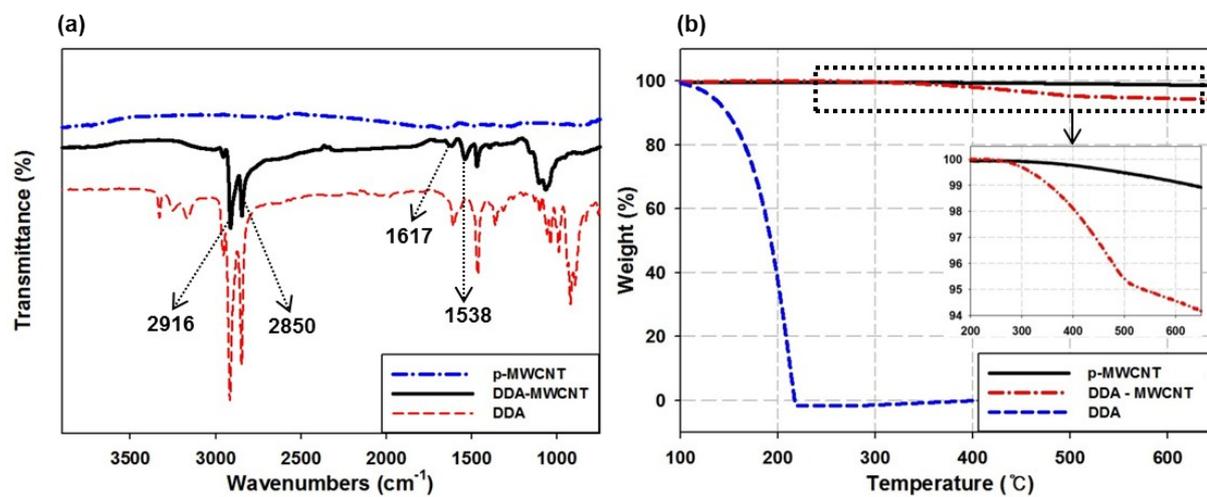


Fig. S6 (a) FT-IR spectra and (b) TGA curves of p-MWCNT, DDA-MWCNT, and DDA. DDA-MWCNTs were prepared by the reaction of o-MWCNT (treated with acid for 15 min) with DDA.

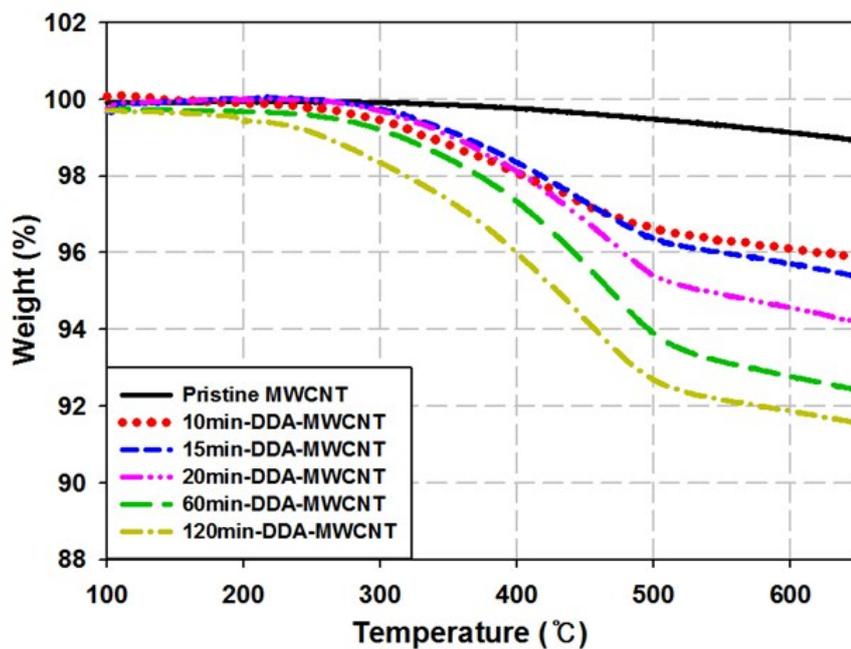


Fig. S7 TGA curves of p-MWCNT and DDA-MWCNTs. DDA-MWCNTs were prepared by the reaction of o-MWCNT (treated with acid for 10, 15, 20, 60, and 120 min) with DDA.

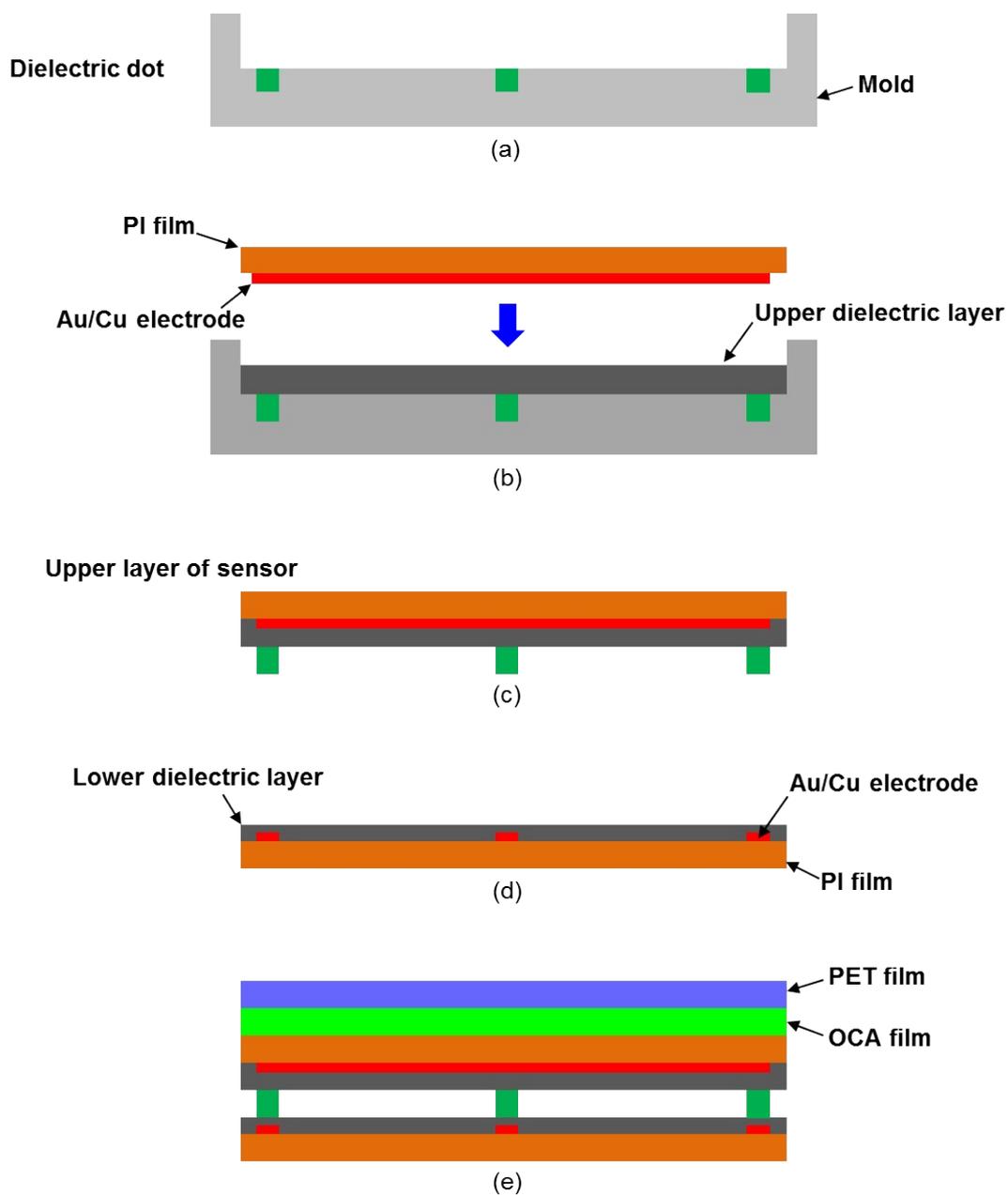


Fig. S8 Schematic illustration of sensor array fabrication. (a) Formation of dielectric dots, (b) bonding of dielectric dots with upper dielectric layer, (c) fabricated upper layer of the sensor, (d) lower layer with dielectric layer, and (e) alignment of upper layer with lower layer.

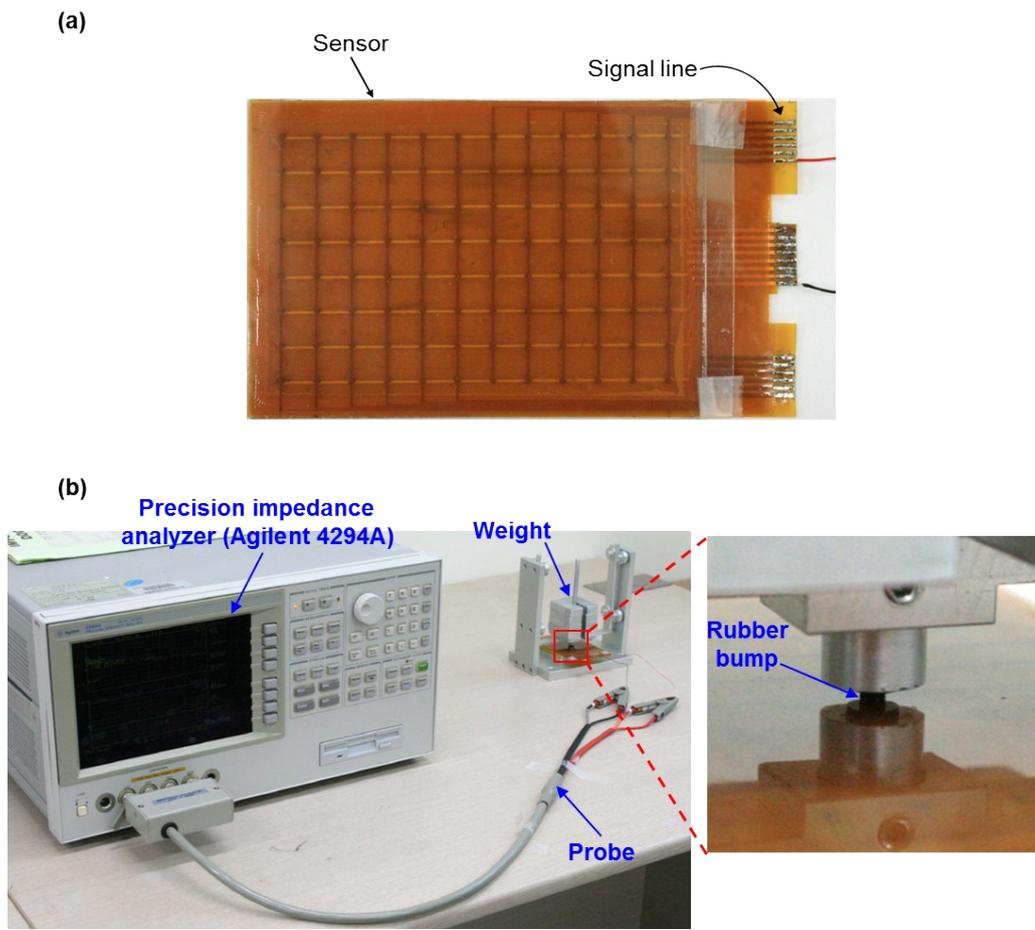


Fig. S9 (a) Bonding of signal processing board with sensor array and (b) measurement setup for loading test as a function of weight.

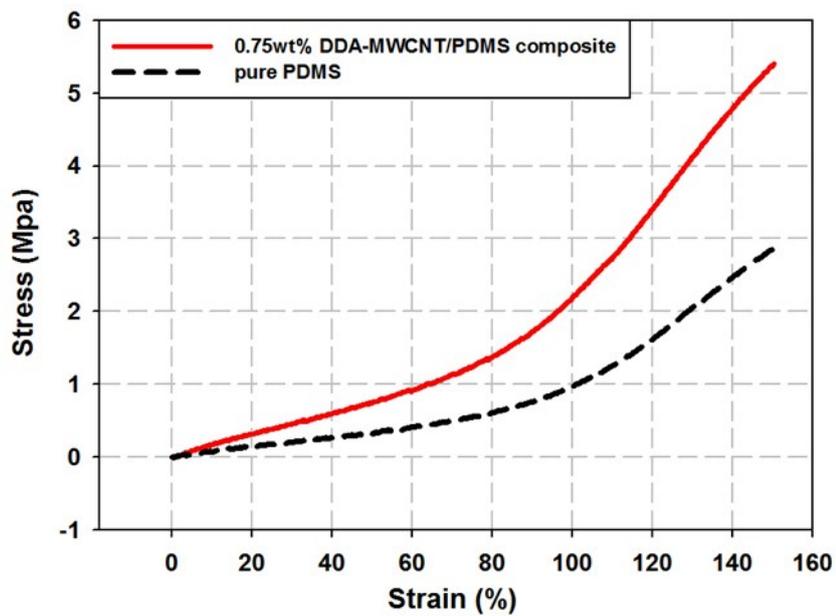


Fig. S10 Stress-strain curves of pure PDMS and PDMS composite with 0.75 wt% DDA-MWCNTs.